# **ASYMMETRICAL DETERMINISTIC LATERAL DISPLACEMENT GAPS FOR DUAL FUNCTIONS OF ENHANCED SEPARATION AND THROUGHPUT OF RED BLOOD CELLS**

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## Supplementary Information 1: The revised  $D_c$  value of different downstream and lateral gap from the **revised** *ε* **formula**



**Supplementary Table-S1: COMSOL parameters for DLD resistance and throughput computational modeling.**

## **Supplementary Information 2: The device specifications and calculations**



**Supplementary Figure-S1: Device dimensions and specifications in the mask design**. The dimensions of the DLD device is approximately 39 mm. Three DLD devices were made with differing gap sizes of 9:9, 9:4 and 4:9 respectively. The mask designs are shown in the figure.

Supplementary Information 3: The revised  $D<sub>c</sub>$  value of different downstream and lateral gap from the **revised** *ε* **formula** 

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\lambda_L = G_L + D_p
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\lambda_d = G_D + D_p
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$$
Old \varepsilon = \tan \theta
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$$
Revised \varepsilon = \frac{(G_D + D_p)\tan\theta}{G_L + D_p}
$$



**Supplementary Table-S2: old epsilon and revised epsilon calculation for asymmetric gap DLD with the old and revised D<sub>c</sub> calculation**. In the simulation, Pillar diameter of 15µm and gradient of 2.82 degree are used. we fixed lateral gap of 15μm, and varied the downstream gap from 2.5 to 15μm and subsequently varied the lateral gap from 2.5 to 15 μm while the downstream gap is fixed at 15μm. We can see that the old ε values are all the same as the gradient values are equal. However, in revised  $\varepsilon$ , the values of row shift fractions are different as it takes into account of both downstream gap and lateral gap. It can be observed that the revised epsilon values go smaller as the downstream gap sizes are reduced compare to the higher epsilon values when the lateral gap sizes are reduced. In the revised epsilon, pillar diameter influences the row shift fraction as the larger pillar diameter requires longer distance for a pillar to be shifted by one period.

To calculate the revised Dc, the revised  $\varepsilon$  is used for the equation  $D_c=1.4 g \varepsilon^{0.48}$  where  $g$  = lateral gap. This lateral gap  $g\,$  is the same as G $_{\rm L}$ . Compared to the old Dc, DLD parameters with  $G_L$ :  $G_D\,>1$  showed enhancement while the old Dc would remain unchanged no matter how small  $G_D$  gets. This was the case for Davis et al where using the old formula regardless of  $G_D$  would result in an inaccurate expectations or "overkill" DLD separation parameters for particle separation.<sup>1</sup> On the contrary,  $G_L: G_D < 1$  showed much better enhancements to Dc as compared to  $G_L: G_D \, > 1.$  This was counter intuitive and needed to be thoroughly

investigated.



**Supplementary Figure-S2: Graph of normalized vertical gap (GD) vs normalized resistance.**

For cases where  $G_L: G_D > 1$  such that  $G_D$  is smaller than  $G_L$ , the resistance increases linearly as  $G_D$ becomes smaller. The gradient is negative. For  $G_L:G_D < 1$ , the resistance increases exponentially when the lateral gap decreases.

## **Supplementary Information 5: Sample input distribution for various DLD devices.**



**Supplementary Figure-S3: Input sample spectrums for beads and RBCs. The figure shows the input separation of beads and RBC for** *9µm : 9µm , 4µm : 9µm and 9µm : 4µm.*

We have additionally added the data analysis of the mean and standard deviation of the



spectrum based on mean sub-channel position and corresponding SI values.

**Supplementary Table-S3: Tabulating the mean separating input and output sub-channel position for the respective samples of beads and RBC.**

We have included 1.5 micron beads in this data to show that particle size smaller than 2.0

microns have similar separation spectrum as 2.0 microns.



#### **Supplementary Table-S4: Coressponding SI values of the separation.**

In order to compare the various separation results between pillars, a separation index is used. The strength and quality of separation is expressed in the magnitude of the index while the resolution is denoted in the standard deviation. The advantage of using an index is to have a standard method of comparison between various devices across all DLD experiments regardless of the number or length at output positions.

The formula for the index is as follow:

Sample Displacement – Initial Sample Position Max Sample Displacement — Initial Sample Position  $\times$  100

Separation Index (SI) =  $\frac{X - X_{Input Mean}}{22 - X_{Input Mean}} \times 100$  ---------- (Supplmentary Eq. 1)

 $\overline{X}$  = the mean deviation of the sample stream as depicted in the graphs.

## **Supplementary Information 7: Secondary DLD experiment to test the separation of 15:30 and 30:15 DLD devices.**

The device were fabricated using standard lithography methods of negative photo resist in SU-8 mold. A photomask was sent for printing and used to pattern SU-8 2025 on a 4" silicon wafer. The SU-8 2025 was spin at 3500 rpm and soft backed at 95°C for 10 mins. The resulting thickness of the SU-8 mold on the wafer is approximately 20 µm thick. The mask was attached to a mask aligner and the wafer was exposed to 365nm UV light for a total energy exposure of 140 mJ/cm<sup>2</sup>. The post-exposure back was performed at 95°C for 2 mins and the patterns were developed under the SU-8 developer wash for 5 mins. The mask designs are as follow:



#### **Supplementary Figure-S4: Mask design of a 15:30 and 30:15 DLD device.**

After the SU-8 mold is complete, we pour a PDMS mixture of 1:10 curing agent to polymer agent into the SU-8 mold, degas the device and let the PDMS cure at 75 °C for 1 hour. Three reservoir holes and a tubing insert hole were punched at the inlet and outlet respectively. The PDMS device was bonded into a glass slide using oxygen plasma surface activation. The once the device is ready, the same priming and surface treatment techniques were used for these devices.



**Supplementary Figure-S5: comparison of Dc characterization between 15x30 and 30x15 gap size.** We characterized the device of 15x30 and 30x15 with gradient of 2.82 $^{\circ}$  by flowing polystyrene beads of 7, 8, 9, 10, and 12μm in size using pluronic 1% buffer with shaded blue region as inlet positions. It can be seen from figure above that the critical diameter of both devices are similar as beads particle equal and larger than 9μm beads are started to go in bumping mode. This means that the downstream gap also contributes to the critical diameter of the device which is not reflected on DLD empirical formula.

Due to the device being bigger, a larger 1 ml syringe is used and the flow rate could be easily increased to

1 µl/ml. The separation spectrum of the devices are shown here in Figure-S3 which was captured using the highspeed camera and tabulated. The results showed great similarity to separation results of 4:9 and 9:4 DLD devices. They have the same Dc and similar separation efficiency and the revised Dc accurately predict the separation in the 30:15 device ( $D_c = 8.15 \,\mu m$ ). Particles less than 8.15 $\mu$ m cannot be separated in the device.

#### **Supplementary Information 8: DLD devices were very prone to clogging of RBCs**



**Supplementary Figure-S6: Clogged device input region of the 4:9 DLD device.**

The figure shows two 1x PBS buffer solution sandwiching the RBC sample stream of region 1 to 5 marked

by the two dots. Due to the clogging, some of the RBC sample stream overflow into the other input sub-

channels. Because the RBCs are much larger than the gap size, they tend to clog even if most cells can

squeeze through. Once a pore is blocked, there is increase chance of aggregation of more RBCs.



**Supplementary Figure-S7: Gap size calculation for PDMS 9:3.**

The G<sub>D</sub> was reduced to approximately 3µm. The PDMS device was fabricated using an SU-8 mold. The SU-8 mold was made using the same photo mask. The fabrication techniques used were the same as Supplementary Information 7 except that the SU-8 used was SU-8 2010 and the SU-8 was spun at 2500 rpm which resulted in approximately 12 µm. This device has the same design except that it has a smaller gap size due to shrinkage of the PDMS.

## **Supplementary Movie 1: Comparing the flow movements of RBC in different DLD devices of 9µm : 9µm, 9µm : 4 µm and 4µm : 9µm.**

The flow movements were captures at different frame rates but sync together to allow ease of viewing.

## **References:**

1 Davis, J. A. *et al.* Deterministic hydrodynamics: taking blood apart. *Proceedings of the National Academy of Sciences of the United States of America* **103**, 14779-14784.